

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant:	Seok-Yoon YANG, et al.	)	
		)	Group Art Unit: 1795
Serial No.:	10/675,455	)	
		)	
Filed:	September 30, 2003	)	Examiner:
		)	Walke, Amanda C.
For:	PHOTOSENSITIVE RESIN COMPOSITION	)	
	CONTROLLING SOLUBILITY AND PATTERN	)	Confirmation No. 5598
	FORMATION METHOD OF DOUBLE-LAYER	)	
	STRUCTURE USING THE SAME	)	

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO FINAL OFFICE ACTION  
UNDER 37 CFR § 1.116, WITH AMENDMENT**

Dear Sir:

In response to the Final Office action mailed on July 10, 2008, Applicants request reconsideration in view of the following remarks for entry in the above-identified application. This reply is being submitted with a Petition of one-month extension of time. Please charge an appropriate extension fee to Deposit Account No. 06-1130.

**Listing of the Claims** currently on file begins on page 2 of this paper; and  
**Remarks** begin on page 6 of this paper.

**Attachments:** Certified English translation for Korean Patent Application No. 10-2002-0060500 filed on October 4, 2002.